

BEST AVAILABLE COPY**PATENT NUMBER and
ISSUE DATE****U.S. UTILITY Patent Application**

APPL NUM 10038375	FILING DATE 01/04/2002	CLASS 438	SUBCLASS 620+	GAU 2812	EXAMINER Sair Kar
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**APPLICANTS: Kim Jae; Lee Sang; 2821

**CONTINUING DATA VERIFIED:

** FOREIGN APPLICATIONS VERIFIED:

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PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed 35 USC 119 conditions met	<input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> yes <input type="checkbox"/> no	ATTORNEY DOCKET NO 30205/37916
Verified and Acknowledged Examiner's initials		
TITLE : Chemical mechanical polishing slurry and process for ruthenium films		
U.S. DEPT. OF COMM./PAT. & TM-PTO-436L (Rev. 12-94)		

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
Assistant Examiner		Total Claims	Print Claims for CLAS
Primary Examiner		DRAWING	
PREPARED FOR ISSUE		Sheets Drawn	Fig.s Drawn
TERMINAL		Print Pg.	
DISCLAIMER		Application Examiner	
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